

RF manipulations with high intensity effects in SIS-100



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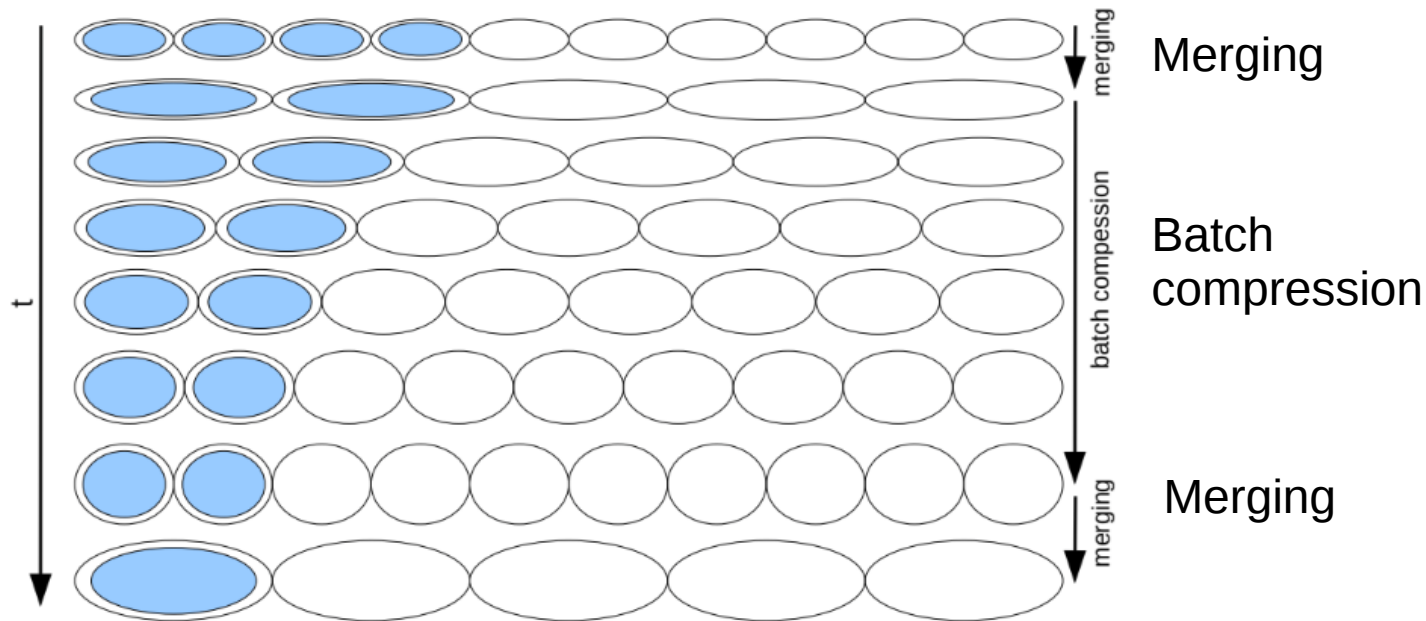
Outline

- Introduction
- Bunch merging with constant bunching factor (because of transverse space charge tune shift)
- Key parameters: rf voltage ramps, phases and merging time
- Intensity effects: Longitudinal space charge and cavity beam loading
- Simulation of the full single bunch generation with intensity effects.
- Summary

Introduction

- In SIS-100, for proton operation, four bunches are merged to one bunch:

- 1) First merging: 4 bunches ($h=10$) \longrightarrow 2 bunches ($h=5$)
- 2) Batch compression: 2 bunches compressed ($h=5$ to 10)
- 3) Second merging: 2 bunches ($h=10$) \longrightarrow 1 bunch ($h=5$)



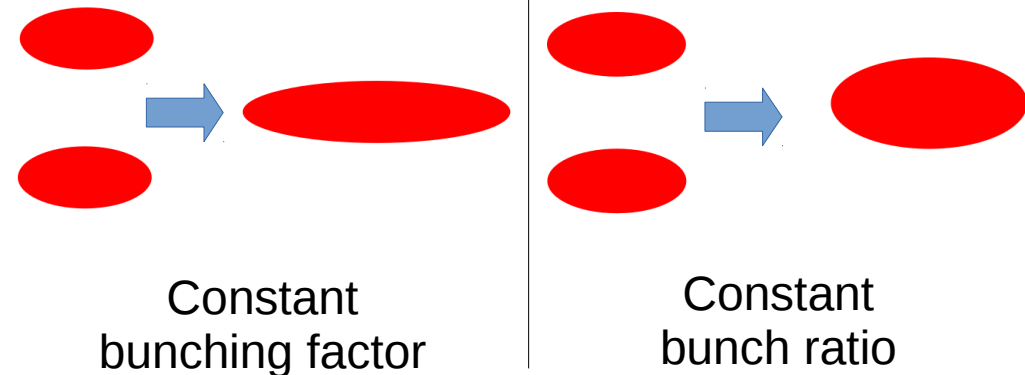
Bunch merging with constant bunching factor

- Bunching factor defined as $B_f = \frac{\text{bunch length}}{\text{bucket length}}$

- After bunch merging $\epsilon_{L,f} = 2\epsilon_{L,i}$

→ Bunch length: $\hat{l}_f = 2\hat{l}_i$

→ Momentum spread $\hat{\delta}_f = \hat{\delta}_i$



- Advantage:
Lower tune shifts;
Lower rf voltage ramps.

	Before merging	After merging
Constant bunching factor	0.26 (0.07, 0.12)	0.26 (0.07, 0.12)
Constant bunch ratio	0.26 (0.07, 0.12)	0.18 (0.11, 0.18)

← Bf
← $(\Delta Q_x, \Delta Q_y)$

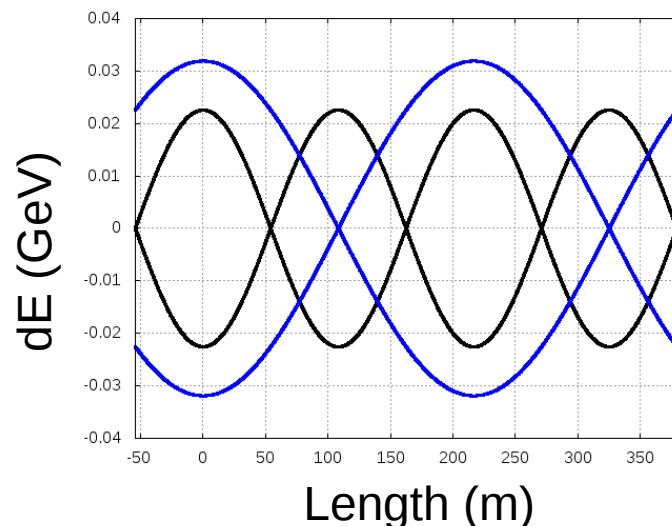
An example of bunching factor and tune shift

Longitudinal settings for bunch merging

- Three key parameters: required rf voltage ramps, phases, and merging time.
- First bunch merging (from h10 to h5)

$$V_{\text{rf},i} = 2V_{\text{rf},f}$$

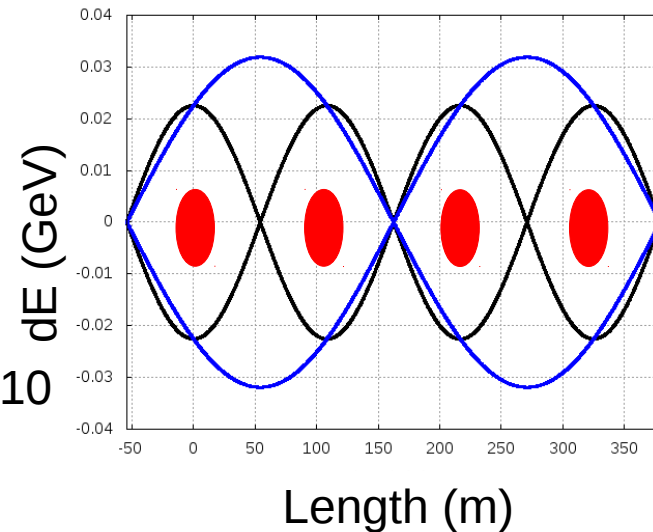
→ Relative phase between h=10 and h=5



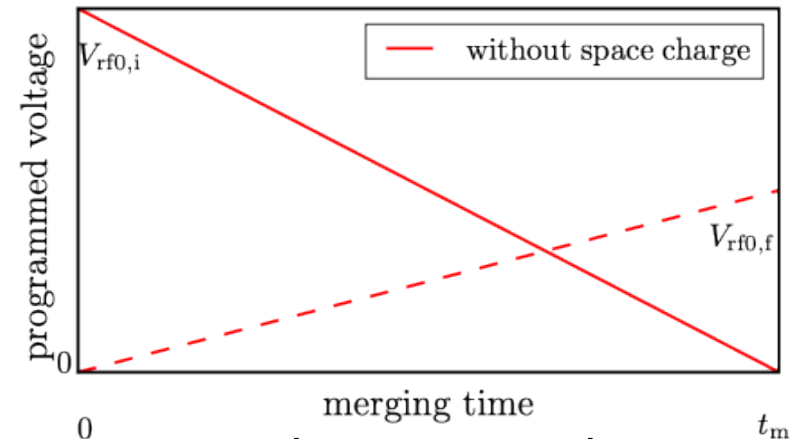
$$\phi_1 = \phi_2 = 0$$

shifted
→

Black = h=10
Blue h = 5



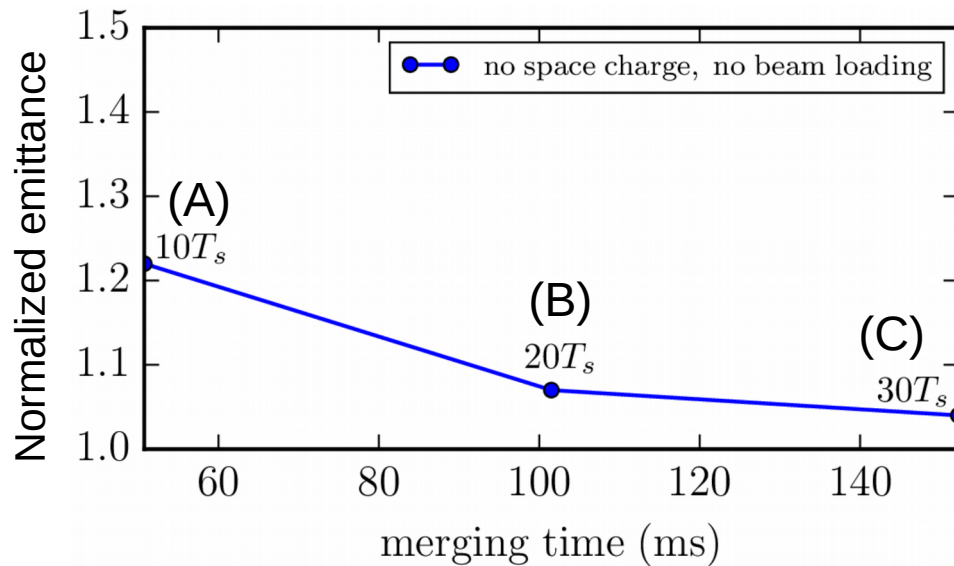
$$\phi_1 = 0, \phi_2 = 90^\circ$$



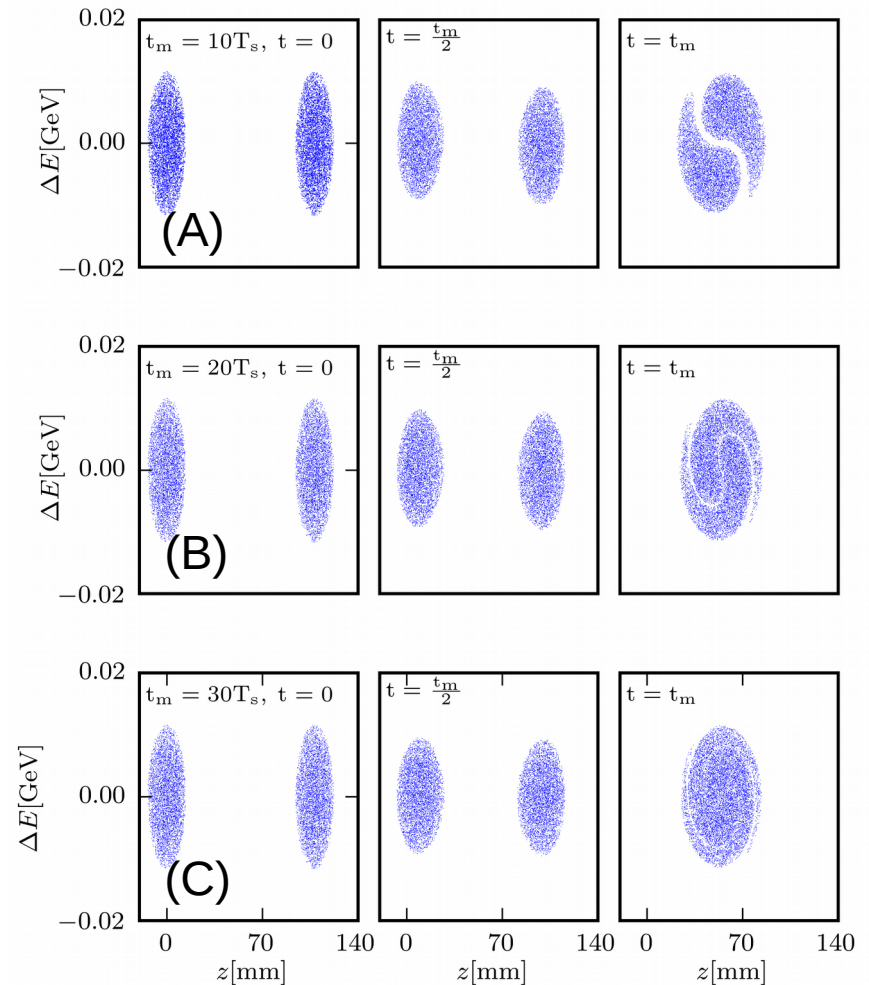
*Voltage ramps in
bunch merging*

Longitudinal settings for bunch merging

- First bunch merging (from h10 to h5)
 - Simulations show that merging time of ~ 100 ms ($20T_s$) can ensure a good emittance

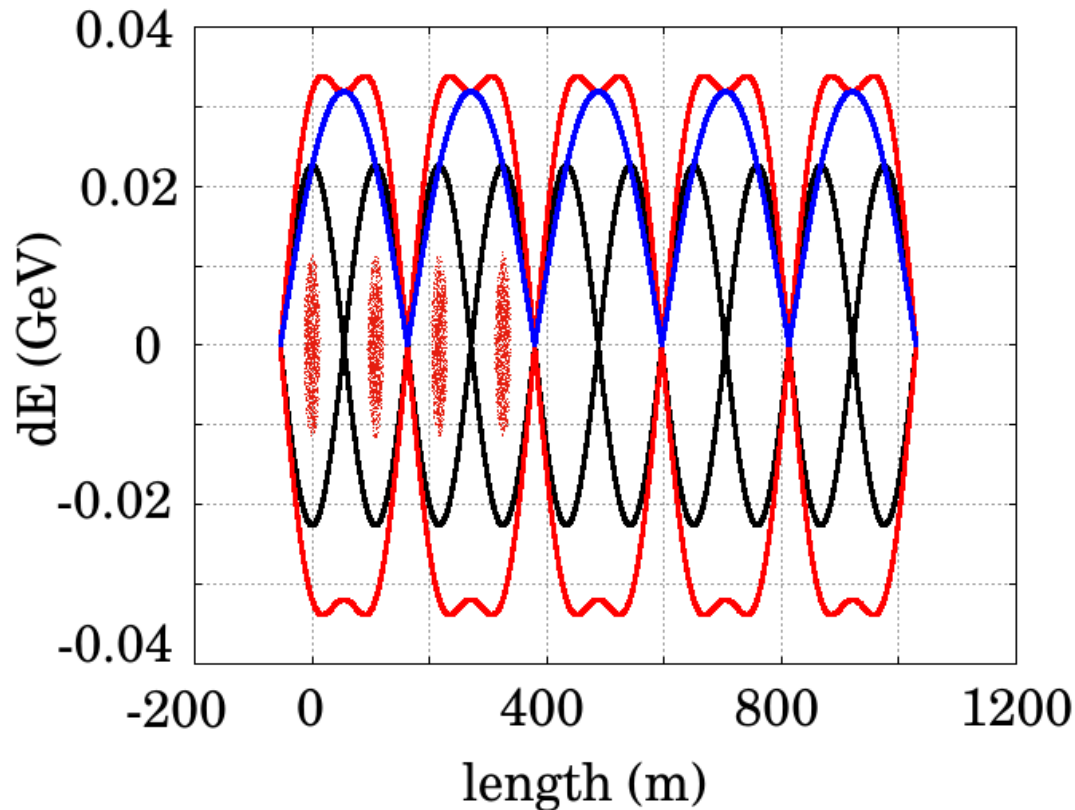


Case	Synchrotron period (T_s)	Turns (n)	time (t_m)
A	10	13800	50.8
B	20	13,300	101.6
C	30	26,600	203.2



Longitudinal settings for bunch merging

- Configuration of the first bunch merging



*Initial bunch merging with harmonic
on $h = 5$ and $h = 10$*

- Simulation code pyORBIT^[1] is employed for rf manipulation with high-intensity effects in SIS-100

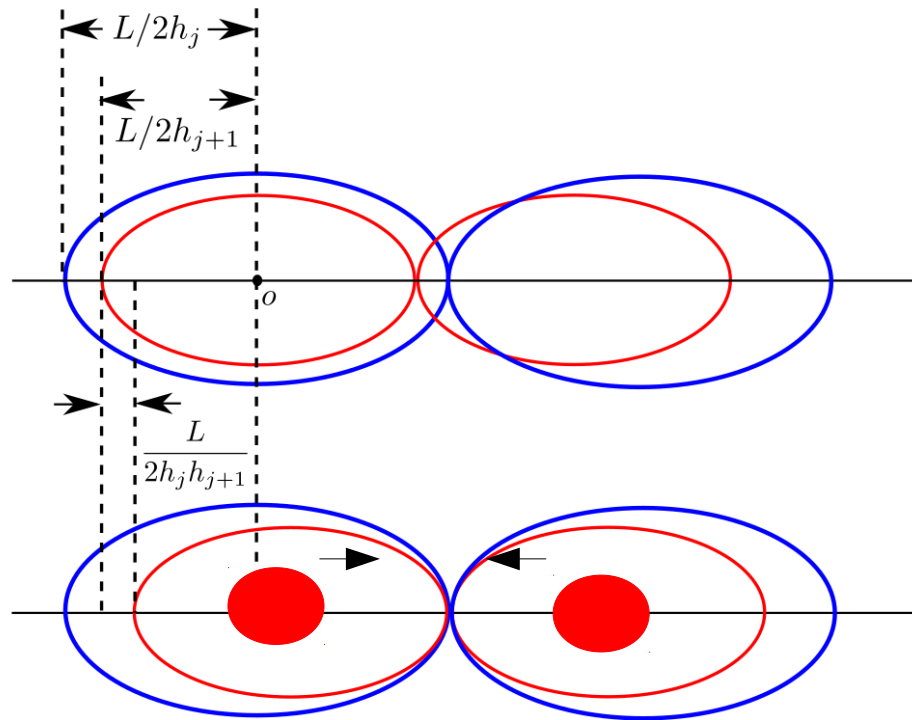
Black $h=10$;
Blue $h=5$;
Red combined

[1] A. Shishlo, S. Cousine, J. Holmes, T. Gorlov, "The Particle Accelerator Simulation Code PyORBIT", 1272, Procedia Computer Science (2015)

Longitudinal settings for batch compression

- Batch compression (from h5 to h10)
- Phases:
 - (1) Since two bunches shrinking symmetrically both the harmonics should be centered to the center of bunches.
 - (2) Different bunch positions.

$$\phi_k = \frac{L}{2h_j h_{j+1}}$$



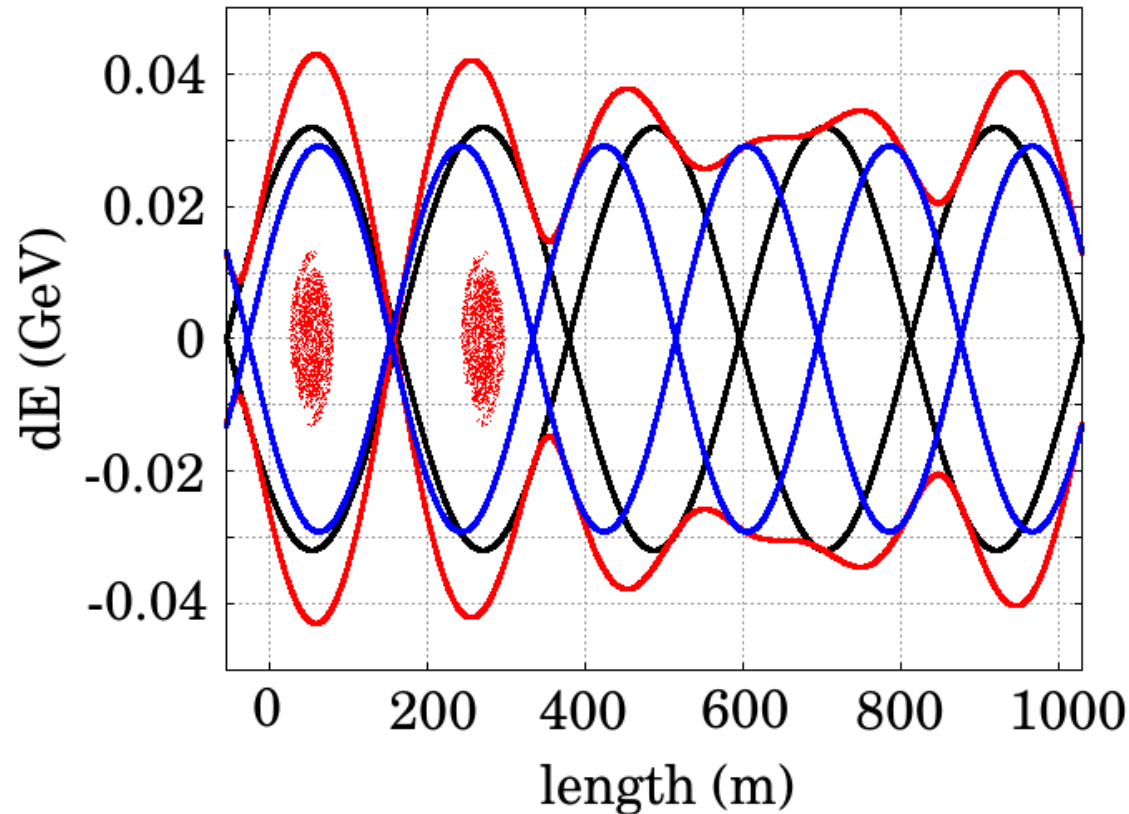
Phase shifts (deg)	Shift for bunch position	Shift for symmetry
Φ_5	90	0
Φ_6	108	36
Φ_7	126	72
Φ_8	144	108
Φ_9	162	144
Φ_{10}	180	180

Schematic drawing of the relative phase

Relative phase for batch compression in SIS-100

Longitudinal settings for batch compression

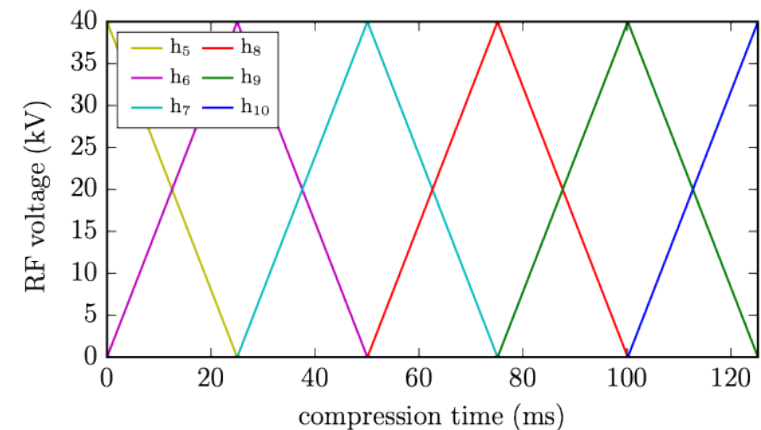
- Configuration of the batch compression (an example of h5 to h6)



*Batch compression with harmonics
on $h=5$ and $h=10$*

Black $h=5$; Blue $h=6$; Red combined

- The emittance growth is less sensitive to the rf voltage than merging.



Longitudinal settings for second bunch merging

- Final merging (from h10 to h5)
 - Similar to the first merging, phase shifts is

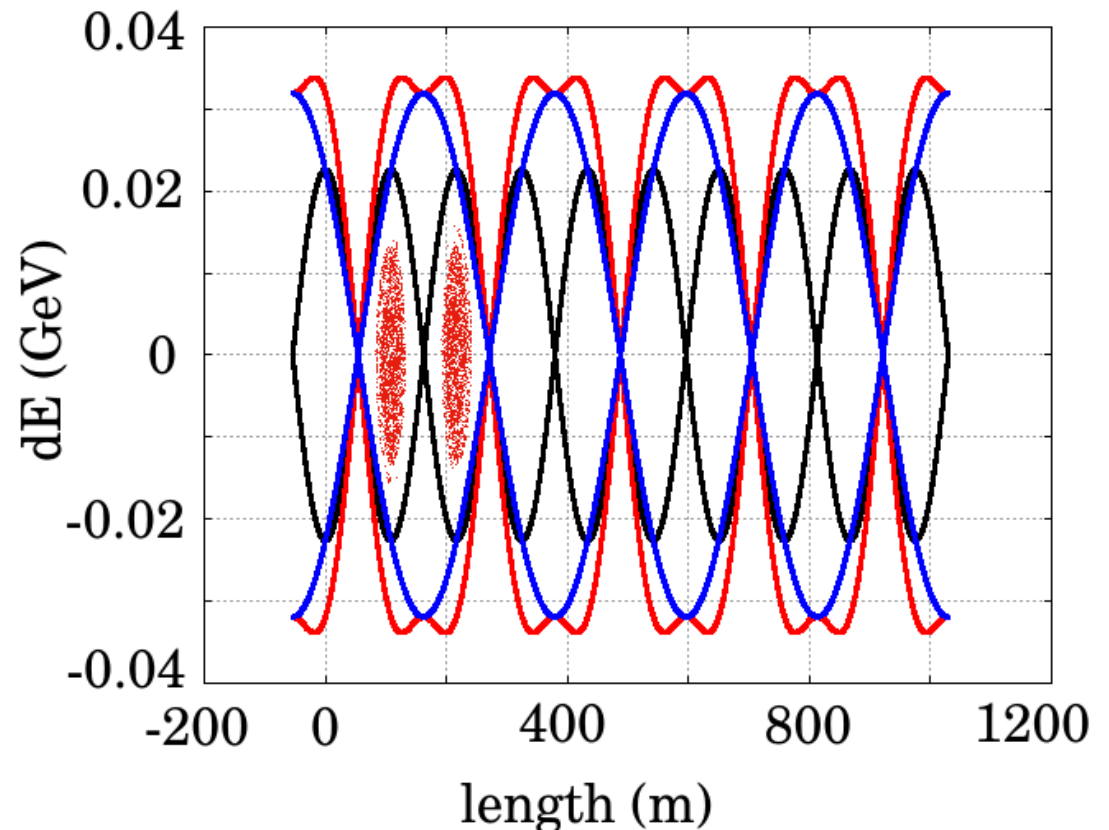
$$\phi_{10} = 0^\circ, \phi_5 = 270^\circ$$

- The merging time

$$t_m \sim 105 \text{ ms}$$

- Configuration of the final bunch merging

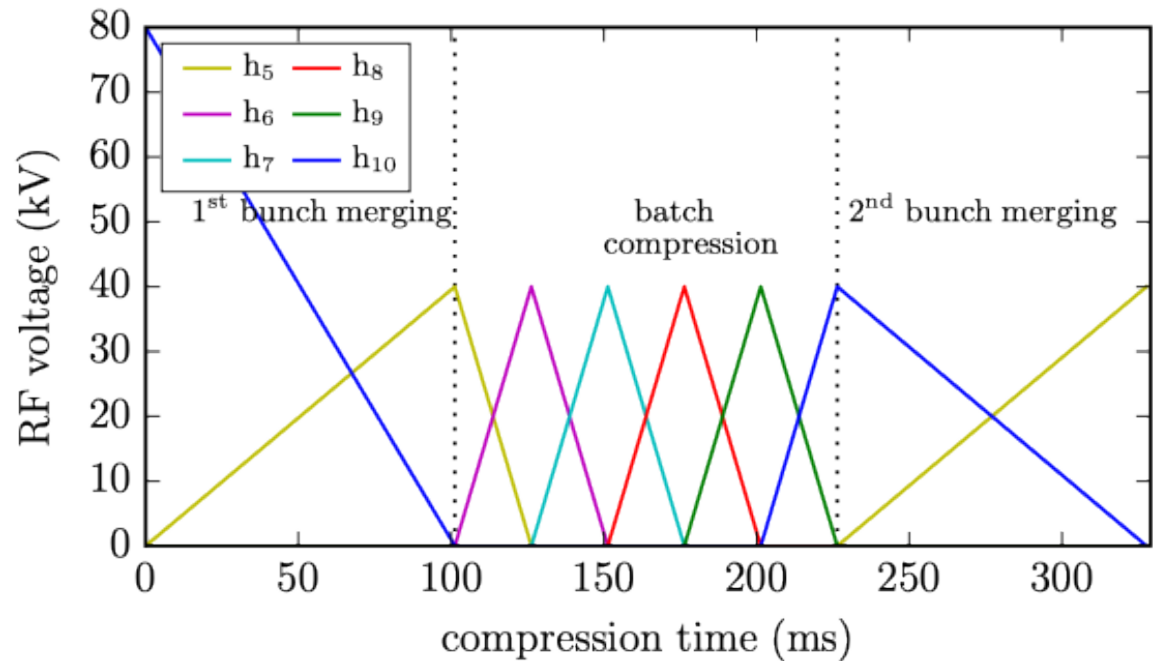
Black h=10;
Blue h=5;
Red combined



*Final bunch merging with harmonic
on $h = 5$ and $h = 10$*

Full rf manipulation without intensity effects

- Proposed voltage waveform for rf manipulation



- Transverse tune shifts

	Initial value	First merging	Batch compression	Final value
Bunching factor	0.26	0.26	0.45	0.36
tune shifts (vx,vy)	(0.07, 0.12)	(0.07, 0.12)	(0.09, 0.14)	(0.11, 0.18)

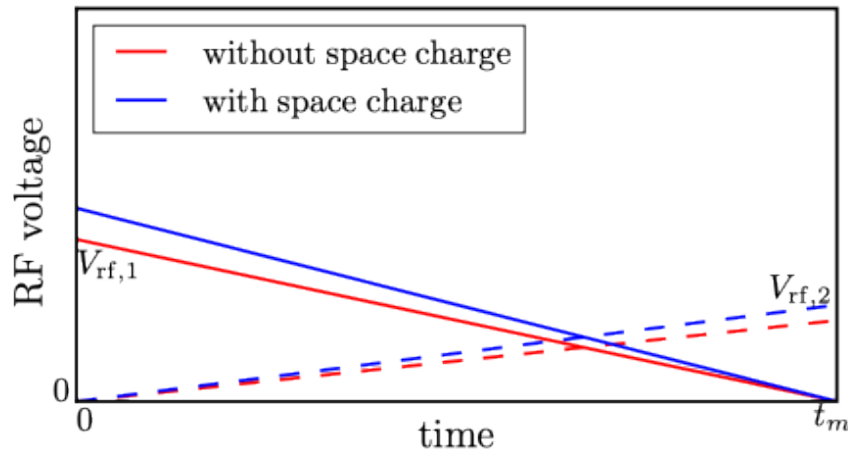
Intensity effects: space charge

- s.c. force can be calculated and matched for specified intensity and emittance
- For SIS100, initial and final s.c. matching s.c.voltage

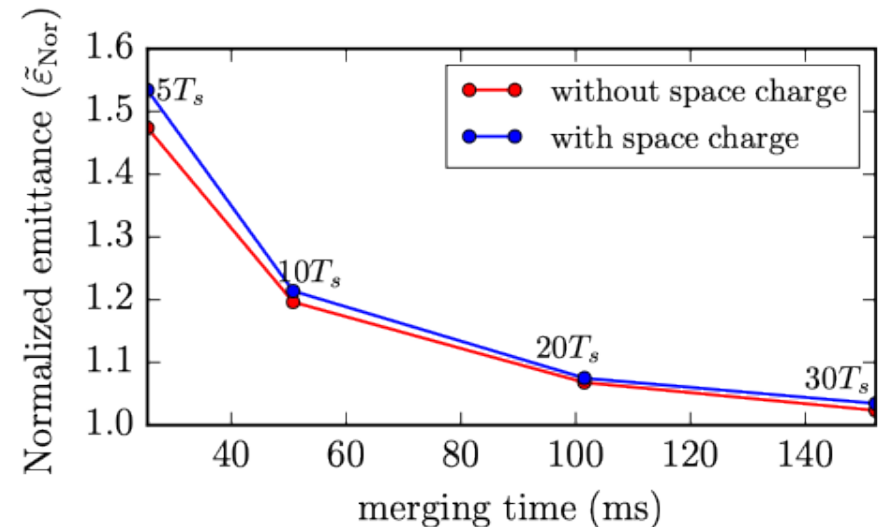
$$V_{\text{rf,sc,i}} = V_{\text{rf,i}} + V_{\text{sc,i}} = 66.0 + 12.7 = 78.7 \text{ kV}$$

$$V_{\text{rf,sc,f}} = V_{\text{rf,f}} + V_{\text{sc,f}} = 33.0 + 6.3 = 39.3 \text{ kV}$$

Space charge can be well compensated.



Designed RF voltage waveform without/with s.c.



Comparison of the final emittance under different merging time without/with s.c.

Intensity effects: beam loading

- The total impedance seen by the beam (RLC model)

$$Z_{bl} = n_1 Z_{bl,i} + n_2 Z_{bl,f}$$
$$= \underbrace{\frac{n_1 R_{sh}}{1 + iQ_{c1}(\omega/\omega_{r1} - \omega_{r1}/\omega)}}_{\text{The first harmonic}} + \underbrace{\frac{n_2 R_{sh}}{1 + iQ_{c2}(\omega/\omega_{r2} - \omega_{r2}/\omega)}}_{\text{The second harmonic}}$$

Resonant freq.

$$\omega_{r1} = h_1 \omega_0 \quad \omega_{r2} = h_2 \omega_0$$

Loaded Q-value

$$Q_{c1} = 10.6 \quad Q_{c2} = 5.3$$

Number of cavities for
constant bunching factor

$$n_1 = 4, n_2 = 2$$

Parameters [unit]	Symbols	Initial value
Resistance [Ω]	R_{sh}	2000
Harmonic number	h	10
Resonant frequency [MHz]	f_{res}	2.72
Loaded quality factor	Q_c	10.6

*Main parameters for beam loading
calculation in SIS-100*

High intensity effects--beam loading

- The beam-induced voltage can cause dipole oscillation.
- Before merging, bunches are assumed to be matched to beam loading, via a shift of the bunch center

$$\Delta\phi_{bl} = a \sin\left(\frac{V_{bl0}}{V_{rf}}\right) \quad (\text{matching shift})$$

- The rf harmonic should be shifted to keep the merging symmetrically

$$\Delta\phi_{hf} = \frac{1}{2}(\Delta\phi_{bl,1} + \Delta\phi_{bl,2}) \quad (\text{symmetry shift})$$

- Symmetry shift will dampen the emittance growth (show later)

Choice of rf cavities

- **First bunch merging: 4 + 2 cavities** (enough for **constant bunching factor**) contributes minimum beam loading effect.

→ 4 cavities on h10, 2 cavities on h5 (80kV, 40kV)

Comparison:
constant ratio
4 + 4 cavities.

- **Batch compression:** less sensitive to beam loading

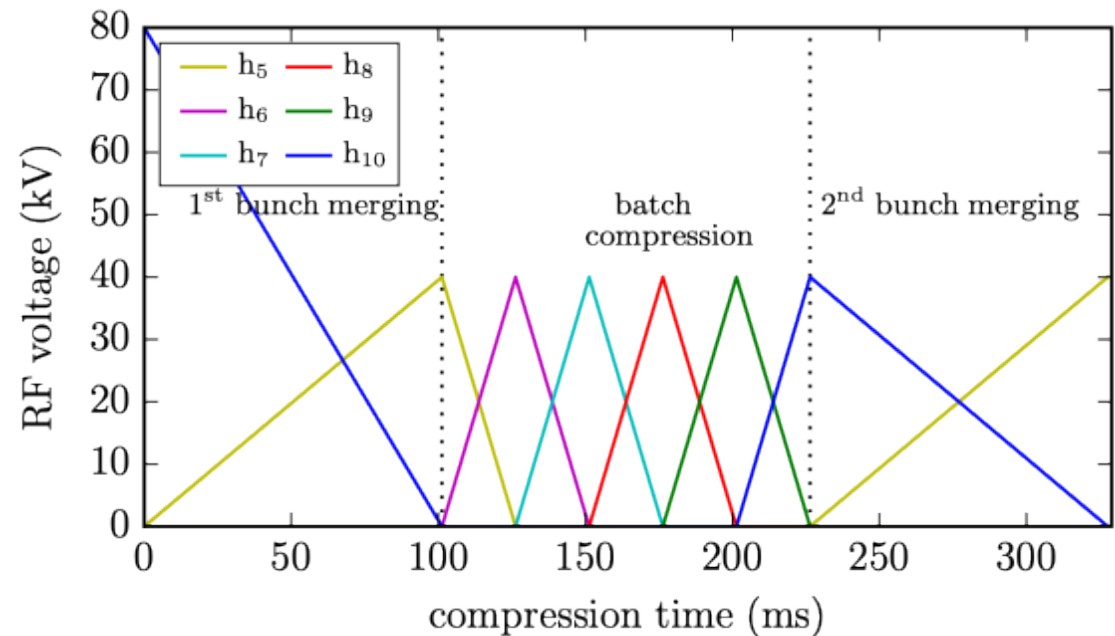
→ 2 cavities (h5 to h10)(40 kV)

- **Final bunch merging**

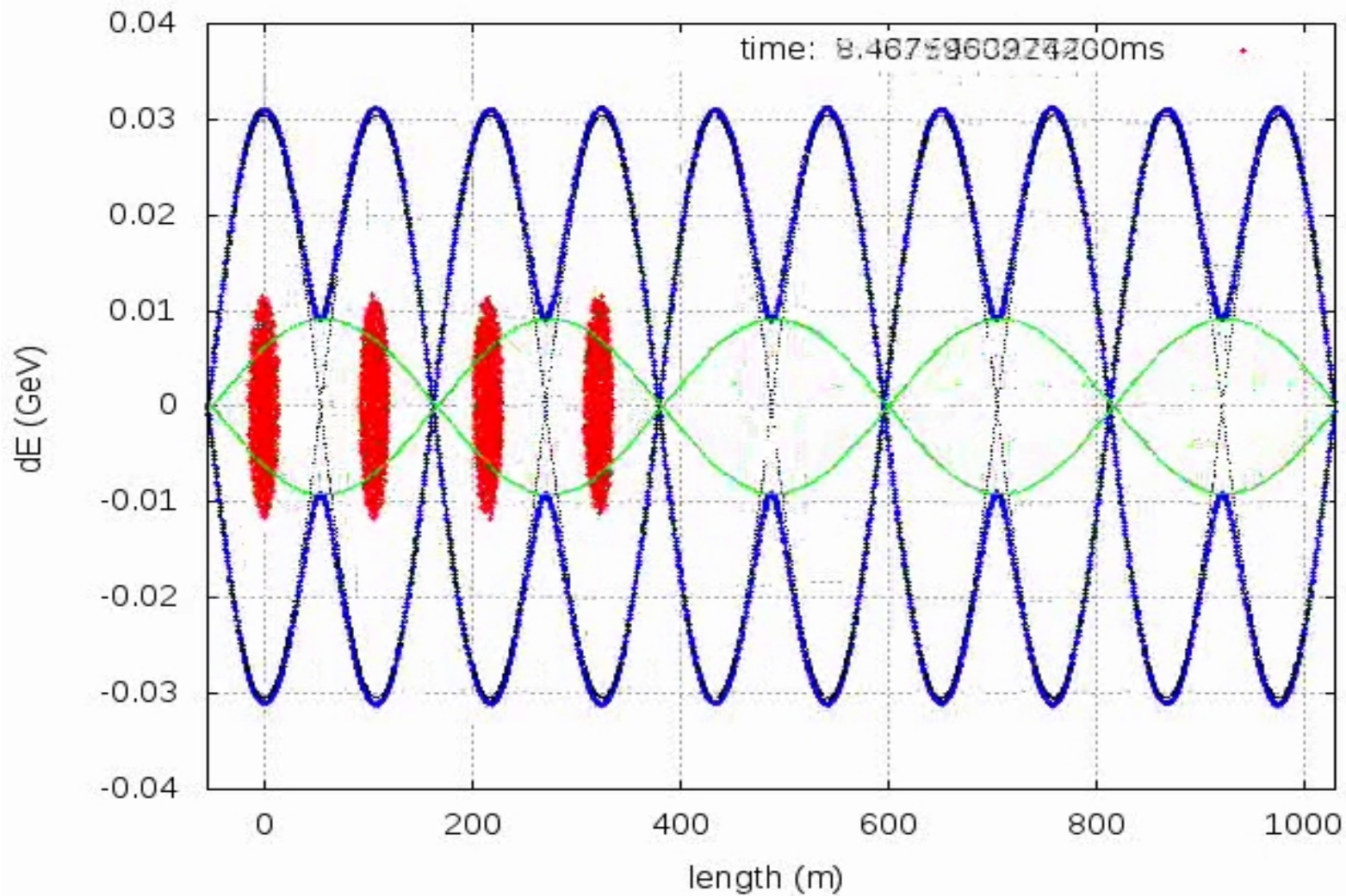
→ 2 cavities on both h5 and h10 (40 kV)

or

→ 2 cavities on h5 and 1 cavity on h10 (40 kV, 20 kV) (low current)

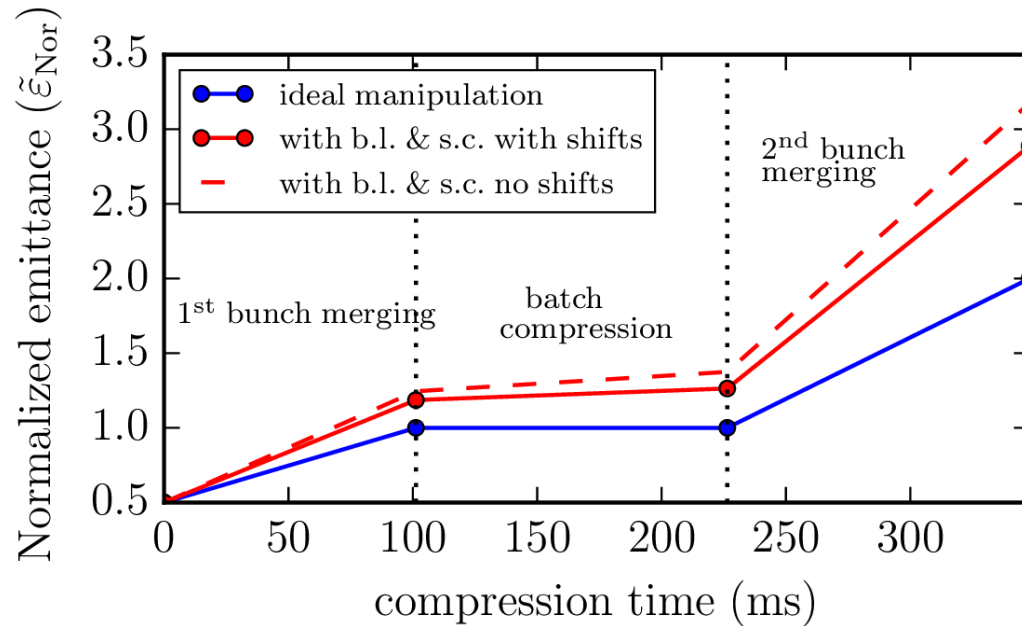


Full rf manipulation with b.l. and s.c.



Movie: Full rf manipulation with high intensity effects

Full rf manipulation with b.l. and s.c.

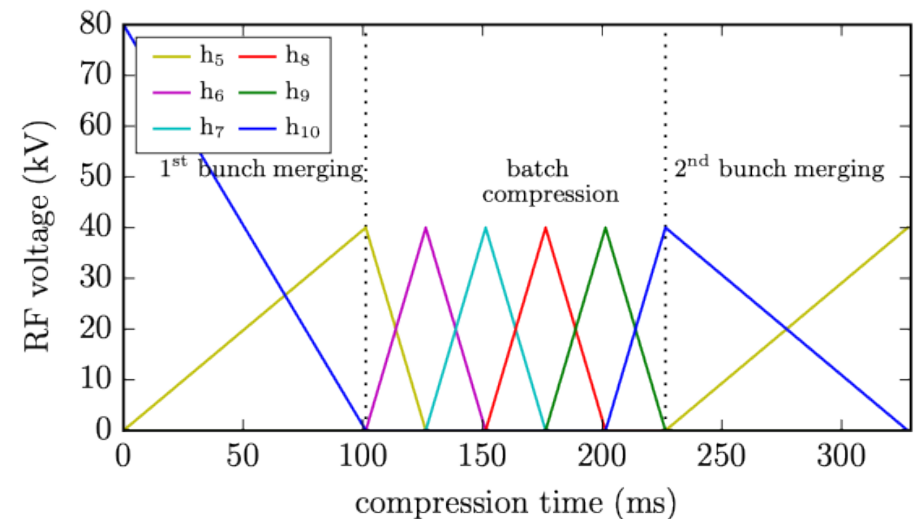


	With shifts	Without shifts
First merging	18.6%	24.5%
Batch compression	26.4%	37.4%
Second merging	44.3%	58.7%

Emittance growth ratio during rf manipulation

Comparison of normalized emittance

RF voltage waveform for bunch manipulation



Summary

- RF manipulation (bunch merging and batch compression) in SIS-100 are investigated by using the simulation code pyORBIT.
- The full rf manipulation towards a single bunch in SIS-100 is shown, using an example ramp.
- Intensity effects (s.c. & b.l.) are included.
- Optimized ramp parameters are used to minimize the emittance growth caused by intensity effects.

Thanks for your attention!

Appendix I Space charge calculation (Elliptical model)

- Space charge voltage is calculated based on the **elliptical model**, in which the space charge forces are linear

- Elliptical model

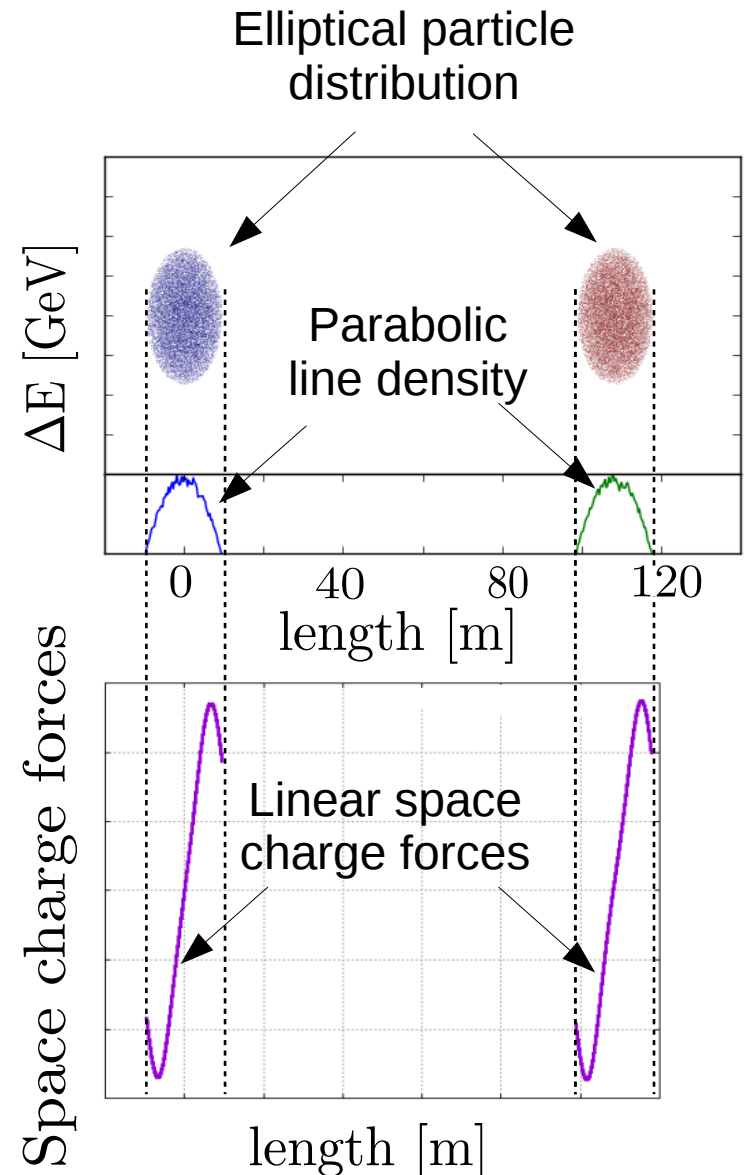


Parabolic line density



Linear space charge forces

- With space charge, the rf voltage should be increased to compensate the space charge defocusing force (voltage)



Appendix II Beam loading calculation model

- The parallel RLC circuit seen by the beam

→ Cavity impedance

$$Z_{bl}(\omega) = \frac{\overset{\text{Shunt impedance}}{R_{sh}}}{1 + \underset{\text{Q-value}}{iQ_c}(\omega/\omega_r - \underset{\text{Resonant frequency}}{\omega_r/\omega})}.$$

→ Beam loading
Induced-voltage

$$V_{bl}(z) = - \sum_{n=0}^{\infty} \overset{\text{beam current spectrum}}{I_n} Z_n e^{inz/R}$$

Appendix III Beam loading matching

- The bunches are matched to beam loading, obtained via a shift

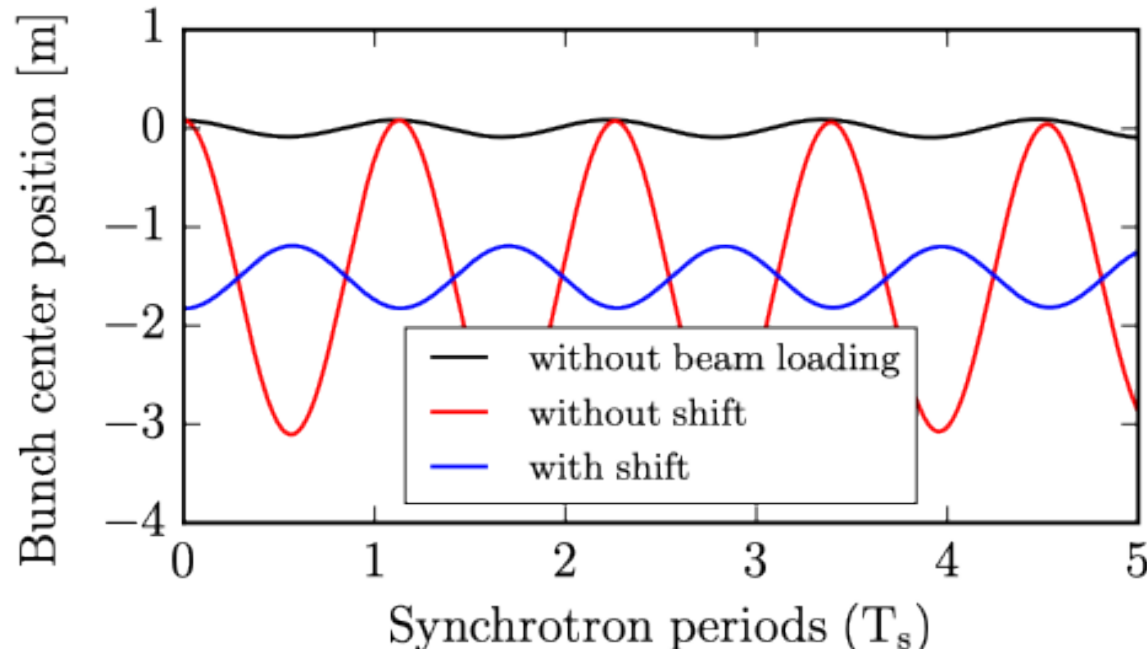
$$\Delta\phi_{bl} = a \sin\left(\frac{V_{bl0}}{V_{rf}}\right)$$

Matching shift

The b.l. voltage at the bunch center

RF voltage

Evolution of the (bunch center) dipole oscillation



Red: b.l., without matching shift

Blue: b.l., with matching shift

Black: no b.l., for comparison

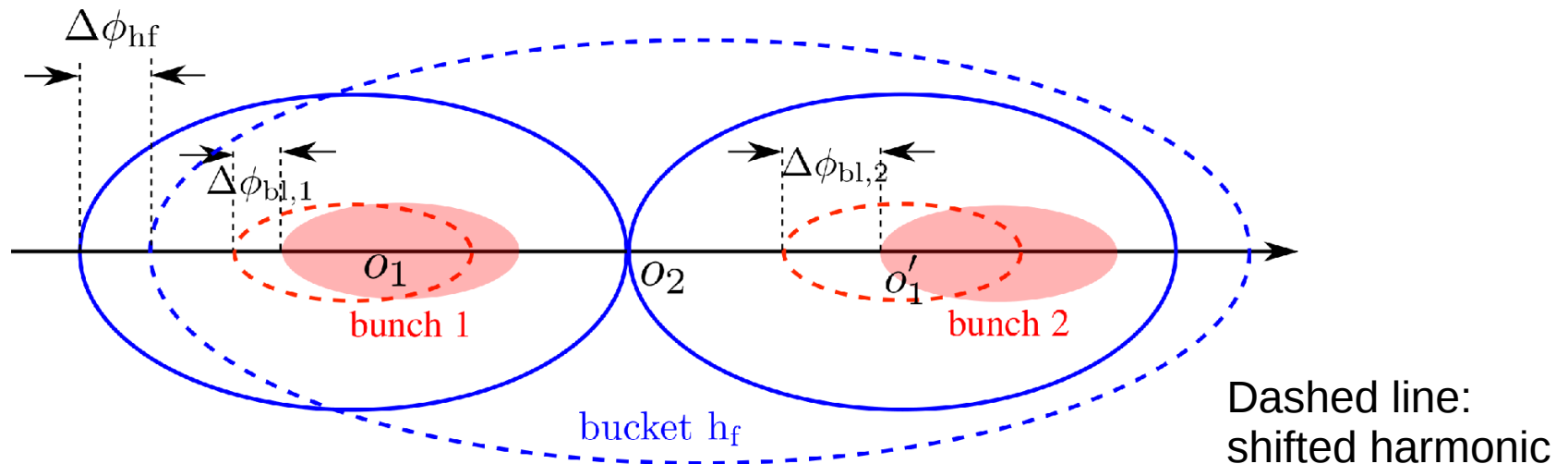
- Beam center oscillation largely reduced by $\Delta\Phi_{bl}$

Appendix IV Beam loading shifts

- The **matching shifts** $\Delta\phi_{bl,i}$ for bunches are different, since the b.l. voltage depends on the positions
- However, $\Delta\phi_{bl,i}$ break the symmetry during bunch merging
- To compensate the symmetry, the **symmetry shift** $\Delta\phi_{hf}$ is added on the harmonics (cavities), satisfying

$$\Delta\phi_{hf} = \frac{1}{2}(\Delta\phi_{bl,1} + \Delta\phi_{bl,2})$$

↑
Symmetry shift



Appendix V: Summary of the last discussion

- Bunch merging with constant bunch ratio
- Space charge can be well compensated via an matched rf voltage.
- Beam loading can be compensated partly via phase shifts.
- Beam loading can cause dipole oscillations, and more serious than space charge.